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PTO/SB/21 (08-03)

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TRANSMITTAL
FORM

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Total Number of Pages in This Submission

Application Number	10/735,110
Filing Date	December 12, 2003
First Named Inventor	Pawan K. Nimmakayala
Art Unit	Unassigned
Examiner Name	Unassigned
Attorney Docket Number	P122/MII-94-69v18

ENCLOSURES (Check all that apply)

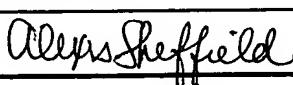
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Remarks		

SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT

Firm or Individual name	Law Office of Kenneth C. Brooks
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Date	3/2/04

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Nimmakayala et al.

PATENT APPLICATION

Serial No.: 10/735,110

Group Art Unit: Unassigned

Filing Date: December 12, 2003

Examiner: Unassigned

For: MAGNIFICATION CORRECTION EMPLOYING OUT-OF-PLANE DISTORTION
OF A SUBSTRATE.

INFORMATION DISCLOSURE STATEMENT

Commissioner
for Patents
Alexandria, VA 22313-1450

Sir:

The following information is submitted in compliance with
Applicants' duty of disclosure under 37 C.F.R. § 1.56. Form
PTO-1449 and a copy of each reference recited below accompanies
this document. It is respectfully requested that the cited
information be expressly considered during the prosecution of
this application, and the references be made of record therein
and appear among the "references cited" on any patent to issue
therefrom.

ISSUED PATENTS

<u>Patent Number</u>	<u>Inventor</u>	<u>Grant Date</u>
4,326,805	Feldman et al.	04/27/1982
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4,929,083	Brunner	05/29/1990
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09/907,512	Sreenivasan et al.	07/16/2001
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FOREIGN PATENT DOCUMENTS

<u>Document No.</u>	<u>Inventor</u>	<u>Pub. Date</u>
DE 2800476	Lamprecht et al.	07-13-1978
JP 1-196749	Matsumoto et al.	08-08-1989
WO 01/79592	Hallberg et al.	10-25-2001
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WO 01/90816	Heidari	11-29-2001

NON-PATENT DOCUMENTS

Chou et al. "Imprint of Sub-25 nm Vias and Trenches in Polymers," *Applied Physics Letters*, 67(21), pp. 3114-3116, 1995.

Chou et al. "Imprint Lithography with 25-Nanometer Resolution," *Science*, vol. 272, pp. 85-87, Apr. 5, 1996.

Haisma, J. et al. "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication," *Journal of Vacuum Science and Technology*, vol. 14, pp. 4124-4128, 1996.

Chou et al. "Imprint Lithography with Sub-10 nm Feature Size and High Throughput", *Microelectronic Engineering* 35, pp. 237-240, 1997.

Feldman et al., "Wafer Chuck For Magnification Correction in X-Ray Lithography," *American Vacuum Society*, pp.3476-3479, 1998.

Scheer, H.C. et al. "Problems of Nanoimprinting Technique for Nanometer Scale Pattern Definition," *Journal of Vacuum Science and Technology*, vol. 16, pp. 3917-3921, 1998.

Colburn, M. et al. "Step and Flash Imprint Lithography: New Approach to High-Resolution Patterning," *Proc. of SPIE*, vol. 3676, pp. 379-389, 1999.

Chou, Stephen et al. "Lithographically-induced Self Assembly of Periodic Micropillar Arrays," *Journal of Vacuum Science and Technology*, vol. 17, pp. 3197-3202, 1999.

Ruchhoeft, P. et al. "Patterning Curved Surfaces: Template Generation by Ion Beam Proximity Lithography and Relief Transfer by Step and Flash Imprint Lithography," *Journal of Vacuum Science and Technology*, vol. 17, pp. 2965-2982, 1999.

Choi, B.J. et al. "Design of Orientation Stages for Step and Flash Imprint Lithography," *Precision Engineering*, vol. 25, pp. 192-199, 2001.

Chou. "Nanoimprint Lithography and Lithographically Induced Self-Assembly," *MRS Bulletin*, pp. 512-517, July 2001.

CERTIFICATE OF MAILING

Respectfully Submitted,
I hereby certify that this paper (along with any paper referred to as being attached or enclosed) is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in a package addressed to: MAIL STOP PATENT APPLICATION, Commissioner for Patents, Alexandria, VA 22313-1450

Signed: Alexis Sheffield
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Date: March 2, 2004

Respectfully,



Kenneth C. Brooks
Reg. No. 38,393

P.O. Box 81536
Austin, Texas 78708-1536
Telephone: 512-527-0104
Facsimile: 512-527-0107
patentsrus@earthlink.net



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Sheet

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of

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Complete if Known

Application Number	10/735,110
Filing Date	12/12/2003
First Named Inventor	Nimmakayala et al.
Group Art Unit	Unassigned
Examiner Name	Unassigned
Attorney Docket Number	P122/MII-94-69V18

U.S. PATENT DOCUMENTS

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶Applicant is to place a check mark here if English language Translation is attached.

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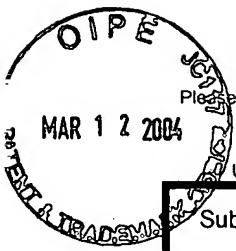
<i>Complete if Known</i>	
Application Number	10/735,110
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First Named Inventor	Nimmakayala et al.
Group Art Unit	Unassigned
Examiner Name	Unassigned
Attorney Docket Number	P122/MII-94-69V18

FOREIGN PATENT DOCUMENTS

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet	3	of	4	Attorney Docket Number	P122/MII-94-69V18
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Complete if Known

Application Number	10/735,110
Filing Date	12/12/2003
First Named Inventor	Nimmakayala et al.
Group Art Unit	Unassigned
Examiner Name	Unassigned

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	B27	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers," Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).	
	B28	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution," Science, Apr. 5, 1996, pp. 85-87, vol. 272.	
	B29	HAISMA et al., "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication," Journal of Vacuum Science and Technology, Nov/Dec 1996, pp. 4124-4128, vol. B 14(6).	
	B30	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput," Microelectronic Engineering, 1997, pp. 237-240, vol. 35.	
	B31	FELDMAN et al., "Wafer chuck for magnification correction in x-ray lithography," American Vacuum Society, 1998, pp. 3476-3479.	
	B32	SCHEER et al., "Problems of the Nanoimprinting Technique for Nanometer Scale Pattern Definition," Journal of Vacuum Science and Technology, Nov/Dec 1998, pp. 3917-3921, vol. B 16(6).	
	B33	COLBURN. et al., "Step and Flash Imprint Lithography: A New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, pp. 379-389, vol. 3676.	
	B34	CHOU et al., "Lithographically-Induced Self Assembly of Periodic Polymer Micropillar Arrays," Journal of Vacuum Science and Technology, Nov/Dec 1999, pp. 3197-3202, vol. B 17(6).	
	B35	RUCHHOEFT et al., "Patterning Curved Surfaces: Template Generation by Ion Beam Proximity Lithography and Relief Transfer by Step and Flash Imprint Lithography," Journal of Vacuum Science and Technology, 1999, pp. 2965-2982, vol. 17.	
	B36	CHOI et al., "Design of Orientation Stages for Step and Flash Imprint Lithography," Precision Engineering, Journal of the International Societies for Precision Engineering and Nanotechnology, 2001, pp. 192-199, vol. 25.	
	B37	CHOU, "Nanoimprint Lithography and Lithographically Induced Self-Assembly," MRS Bulletin, July 2001, pp. 512-517.	

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Sheet 4 of 4

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Application Number	10/735,110
Filing Date	12/12/2003
First Named Inventor	Nimmakayala et al.
Group Art Unit	Unassigned
Examiner Name	Unassigned
Attorney Docket Number	P122/MII-94-69V18

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Signature		Date Considered	
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